

IN THE CLAIMS

This listing of claims replaces all prior listings:

1. (Currently Amended) A method of manufacturing a diffusing reflector comprising the processes of:
 - preparing a substrate;
 - forming a first resin film having photosensitivity on said substrate;
 - providing a gathering of adjacent pillar-shaped bodies isolated from each other through patterning of said resin film with photolithography;
 - deforming gently said adjacent pillar-shaped bodies through a reflow;
 - forming an uneven surface layer having the maximum inclination angle of under 12^0 by coating with a thin layer of a second resin said gently deformed pillar-shaped bodies;
 - covering with the second resin open flat spaces located between said isolated adjacent pillar-shaped bodies to form one concave gap between any two adjacent isolated pillar-shaped bodies so that upper end portions of said any two adjacent isolated pillar-shaped bodies are higher than a lower end portion of said one concave gap in the thickness direction of the diffusing reflector, thereby minimizing an occurrence of a flat surface area on said substrate; and
 - forming a metal film on said uneven surface layer,
 - wherein,
 - said first resin film is patterned by straight connected lines that form a continuous polygonal pattern, said straight lines providing a continuous and substantially uniform gap between ~~thereby formed~~ said polygonal pillar-shaped bodies ~~thereby forming a rectilinear honeycomb-like pattern,~~ and
 - said gap having a size equal to about a minimum resolution of said photolithography,
 - and
 - a thickness of the second resin is about 500nm.
2. (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein said maximum inclination angle is about 10^0 .

3. (Cancelled)

4. (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein said reflow process is a heat treatment under the temperature of about 220⁰C.

5. (Previously Presented) The method of manufacturing a diffusing reflector as claimed in claim 1, wherein gathering of polygonal pillar-shaped bodies isolated from each other by the divided patterning of said first resin film by said photolithography is provided.

6. (Cancelled)